

Title (en)
LINEAR SOURCE FOR VAPOR DEPOSITION WITH HEAT SHIELDS

Title (de)
LINEAREQUELLE ZUR AUFDAMPFUNG MIT HITZESCHILDEN

Title (fr)
SOURCE LINÉAIRE DESTINÉE AU DÉPÔT EN PHASE VAPEUR ÉQUIPÉE D'ÉCRANS THERMIQUES

Publication
EP 3559302 A1 20191030 (EN)

Application
EP 17811303 A 20171207

Priority
• EP 16206181 A 20161222
• EP 2017081926 W 20171207

Abstract (en)
[origin: WO2018114378A1] A long high-temperature high-output linear evaporation source apparatus (200) for atomic vapor deposition of metal atoms suited for the production of CIGS thin films, comprising at least one elongated horizontal crucible (50) for containing, up to a given level in the crucible (50), material (55) to be melted and evaporated, comprising a heater assembly (100) and at least a nozzle (65), comprising at least one heat shield assembly (80, 90) that at least partially surrounds the crucible (50) and comprises at least one shielding layer (83, 93) made of graphite or carbon foam or felt, so as to reduce radiation of heat away from the linear evaporation source (200). This enables to achieve a more even spatial distribution of the deposited material with less energy expense and the possibility to regulate an evaporation profile.

IPC 8 full level
C23C 14/24 (2006.01); **C23C 14/26** (2006.01)

CPC (source: EP)
C23C 14/243 (2013.01); **C23C 14/26** (2013.01)

Citation (search report)
See references of WO 2018114378A1

Designated contracting state (EPC)
AL AT BE BG CH CY CZ DE DK EE ES FI FR GB GR HR HU IE IS IT LI LT LU LV MC MK MT NL NO PL PT RO RS SE SI SK SM TR

Designated extension state (EPC)
BA ME

DOCDB simple family (publication)
WO 2018114378 A1 20180628; EP 3559302 A1 20191030

DOCDB simple family (application)
EP 2017081926 W 20171207; EP 17811303 A 20171207